[WeD3] Computational Lithography & Mask	
Session Date	November 12 (Wed.), 2025
Session Time	16:05-17:45
Session Room	Room D (Sydney Room, 2F)
Session Chair	Prof. Chawon Koh (Yonsei Univ., Korea)

[WeD3-1] [Invited] **16:05-16:35**

EUV and High-NA EUV Patterning for DRAM Scaling: Challenges and Opportunities

Jeonghoon Lee (imec, Belgium)

[WeD3-2] [Invited] **16:35-16:55**

From Molecular Simulations to Artificial Intelligence for Advanced Patterning Materials Designs

Su-Mi Hur (Chonnam Nat'l Univ., Korea)

[WeD3-3] **16:55-17:10**

Pioneering Carboxylated Zirconium Oxo Cluster Resist for Precision Nanoscale Patterning

Seong-Ji Ha, Bo Kyu Kwon, Jinyoung Lee, and Ji-Hyun Jang (UNIST, Korea)

[WeD3-4] [Invited] **17:10-17:30**

MBM-4000: Electron Multi-Beam Mask Writer for Advanced Mask Making

Rieko Nishimura, Hiroshi Matsumoto, Kenichi Yasui, Tomoo Motosugi, Hayato Kimura, and Yoshinori Kojima (NuFlare Technology, Inc., Japan)

[WeD3-5] **17:30-17:45**

Contamination Control Strategies in Next-Generation EUV Pods

Elson Tu, Asheesh Nautiyal, and Chiaho Chuang (Gudeng Precision Industry Co., Ltd., Taiwan)